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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Tony P. Chiang, Karl F. Leeser
Assignee: Angstrom Systems, Inc.
Title: Method and Apparatus for Improved Temperature Control In Atomic Layer Deposition
Serial No.: 09/854,092 Filing Date: May 10, 2001
Examiner: Timothy Howard Meeks Group Art Unit: 1762
Docket No.: PA1663US
(ANS-PA1663US)

San Jose, California
May 7, 2004

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

RESPONSE TO RESTRICTION REQUIREMENT

Dear Sir:

In response to the March 9, 2004 restriction requirement, Applicants hereby elect the claims in Group I (Claims 1-15 and 44-47) drawn to a depositing method, classified in class 427, subclass 255.7, for further prosecution in the above patent application. Applicants reserve the right to prosecute the remaining claims in a divisional application.

Should the Examiner have any questions, the Examiner is invited to call the undersigned at (408) 382-0480.

Certification of Facsimile Transmission

I hereby certify that this paper is being facsimile transmitted to the U.S. Patent and Trademark Office on the date shown below.

Signature

Date

Respectfully submitted,

Brian D. Ogonowsky
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